Title (en)

ELECTROSTATICALLY ASSISTED COATING METHOD AND APPARATUS WITH FOCUSED WEB CHARGE FIELD

Title (de)

ELEKTROSTATISCH ERREGTES BESCHICHTUNGSVERFAHREN UND VORRICHTUNG MIT FOKUSSIERTEM MATERIALBAHNLADUNGSFELD

Title (fr)

PROCEDE ET DISPOSITIF DE REVETEMENT ELECTROSTATIQUE A CHAMP DE CHARGE DE BANDE LOCALISE

Publication

EP 1274515 B1 20060920 (EN)

Application

EP 01922820 A 20010329

Priority

- US 0110033 W 20010329
- US 54436800 A 20000406
- US 54459200 A 20000406

Abstract (en)

[origin: WO0176769A2] A system for applying a fluid coating onto a substrate includes forming a fluid wetting line by introducing a stream of fluid onto a first side of the substrate along a laterally disposed fluid-substrate contact area. An electrical force is created on the fluid from an electrical field (originating from electrical charges which are on the second side of the substrate) that is substantially at and downstream of the fluid wetting line. The electrical field can be generated by charges that have been transferred to the second side of the substrate from a remote charge generator.

IPC 8 full level

B05D 1/30 (2006.01); **B05D 3/14** (2006.01); **B05B 5/14** (2006.01); **B05C 5/00** (2006.01); **B05C 11/10** (2006.01); **B05D 7/00** (2006.01); B05D 1/00 (2006.01); B05D 1/26 (2006.01)

CPC (source: EP KR)

B05C 5/008 (2013.01 - EP); **B05D 1/007** (2013.01 - EP); **B05D 1/30** (2013.01 - KR); **B05D 1/305** (2013.01 - EP); **B05D 3/12** (2013.01 - EP); B05D 3/14 (2013.01 - EP)

Cited by

US9795986B2; US8903298B2

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WO 0176769 A2 20011018; **WO 0176769 A3 20020627**; AT E298272 T1 20050715; AT E340035 T1 20061015; AU 4333301 A 20011023; AU 4958001 A 20011023; BR 0109830 A 20030121; BR 0109830 B1 20110405; BR 0109879 A 20030603; BR 0109879 B1 20110906; CA 2402969 A1 20011018; CA 2404220 A1 20011018; CN 100379498 C 20080409; CN 1429138 A 20030709; CN 1429138 B 20120530; CN 1433340 A 20030730; DE 60111632 D1 20050728; DE 60111632 T2 20060518; DE 60123230 D1 20061102; DE 60123230 T2 20070913; EP 1274515 A2 20030115; EP 1274515 B1 20060920; EP 1280614 A2 20030205; EP 1280614 B1 20050622; EP 1611963 A1 20060104; JP 2003530214 A 20031014; JP 2003530215 A 20031014; KR 100715166 B1 20070511; KR 20030007497 A 20030123; KR 20030007498 A 20030123; MX PA02009842 A 20030527; MX PA02009852 A 20030527; TW 527228 B 20030411; TW 553776 B 20030921; WO 0176770 A2 20011018; WO 0176770 A3 20020228

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